

ABSTRACT OF THE DISCLOSURE

First, an undercoating film made of silicon nitride or silicon nitride oxide is formed on a substrate. Then the undercoating film is subjected to both/either process A of wet-cleaning the undercoating film with a cleaning liquid and/or process B of irradiating ultraviolet light onto the undercoating film. Afterward, an organic thin film is formed on the undercoating film by providing a liquid organic material (a specific organic material is used if only either process A or process B has been performed).